L Number	Hits	Search Text	DB	Time stamp
1	5	(p lysilicon adj tra) and lin r and oxid and sid wall and spacer and (silic n adj nitride) and (L near (shape r shap d or shaping))	USPAT; US-P PUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/07 14:36
2	5	((conductive or conducting or polysilicon) adj trace) and liner and oxide and sidewall and spacer and (silicon adj nitride) and (L near (shape or shaped or shaping))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/07 14:38
3	16	(gate near3 polysilicon) and (source or drain or source/drain) and liner and spacer and (silicon adj nitride) and (l near5 spacer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/07 14:44
4	0	(gate near10 (source or drain or source/drain) near10 liner near10 oxide near10 (silicon adj nitride) near10 spacer near10 (l near (shape or shaped))).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/07 14:45
5	0	(gate near10 (source or drain or source/drain) near10 liner near10 oxide near10 (silicon adj nitride) near10 spacer near10 (l near (shape or shaped)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/07 14:45
6	0	(gate near10 (source or drain or source/drain) near10 liner near10 (insulating or dielectric or oxide) near10 (silicon adj nitride) near10 spacer near10 (l near (shape or shaped)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/07 14:45
7	3	(gate same (source or drain or source/drain) same liner same (insulating or dielectric or oxide) same (silicon adj nitride) same spacer same (l near (shape or shaped)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/07 14:48
8	7	(l near2 (shape or shaped) near3 spacer).clm. and liner.clm. and polysilicon.clm. and gate.clm. and (source or drain or source/drain).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/07 14:59
9	21	(l near2 (shape or shaped) near3 spacer) and liner and polysilicon and gate and (source or drain or source/drain)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/07 15:00